

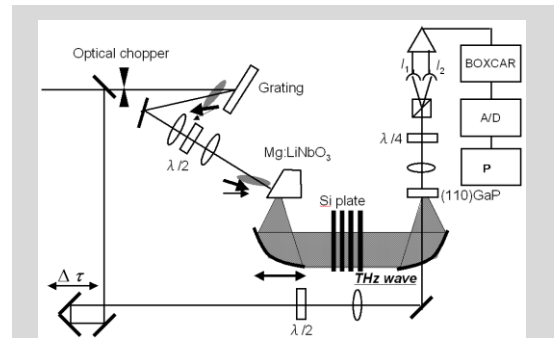
Mg:SLN Prism for THz Generation

Unrivaled New Substrate Crystal for GaN epitaxial growth

Advantages

(Mg:SLN : Mg 1.3mol% doped stoichiometric LiNbO₃)

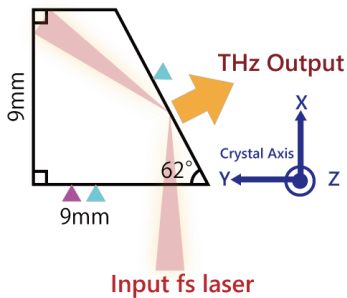
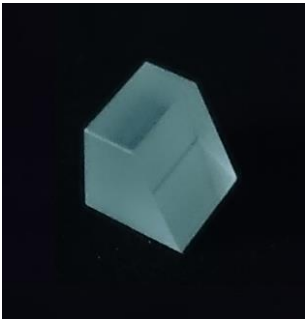
- ✓ Easy setup for THz Generation
- ✓ Wide THz bandwidth (0.2~2.5 THz)
- ✓ Low Defect Density
- ✓ High damage threshold



M. Jewariya, M. Nagai, and K. Tanaka, Journal of Optical Society of America B, 26, (9) A101 (2009).

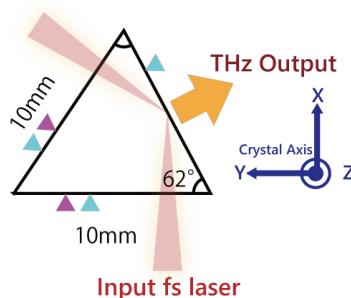
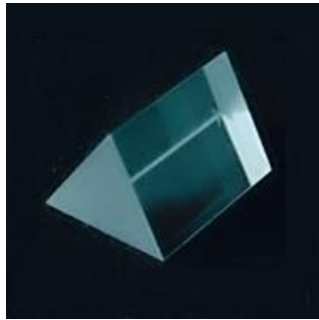
Standard Type1 (Basic)

9 mm x 9 mm x 9 mm



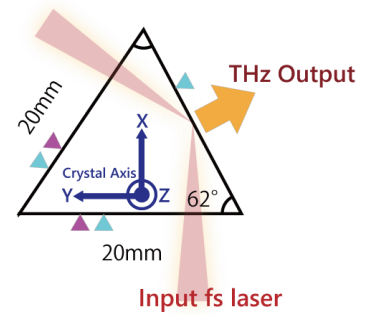
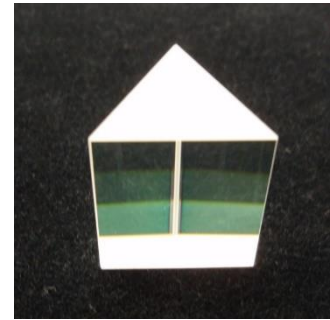
Standard Type2 (High Power)

10 mm x 10 mm x 12.5 mm



Standard Type3 (Large Aperture)

20 mm x 20 mm x 20 mm



- ▲ Optically polished
- ▲ AR coating (for Ti:Sapphire laser and 1um fs fiber laser) @ 780 - 820nm and @1025nm ~ 1065nm

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🐦 Oxide Yamanashi

Detail dimension and specification

Standard Type 1

9mm
9mm
9mm
9mm
62°
62°

- ▲ Optically polished
- ▲ AR coating
R<1.0% @ 780 - 820nm
R<0.5% @ 1025nm ~ 1065nm

Crystal Axis
X
Y ← Z

Standard Type 2

10mm
10mm
12.5mm
10mm
62°
62°

- ▲ Optically polished
- ▲ AR coating
R<1.0% @ 780 - 820nm
R<0.5% @ 1025nm ~ 1065nm

Crystal Axis
X
Y ← Z

Standard Type 3

20mm
20mm
20mm
20mm
62°
62°

- ▲ Optically polished
- ▲ AR coating
R<0.5% @ 780 - 820nm
R<1.0% @ 1025nm ~ 1065nm

Crystal Axis
X
Y ← Z

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